Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

- Claim 1 (withdrawn) A method for producing a light emitting diode, which has a plated substrate with a mirror, comprising steps of:
 - a) providing a substrate with an LED epitaxial structure including a second cladding layer, an active layer, a first cladding layer, a window and a metal contact layer sequentially formed on said substrate;
 - b) etching a part of said LED epitaxial structure to expose said second cladding layer;
 - c) forming a first electrode and a second electrode respectively on said metal contact layer and said exposed second cladding layer, and heating both said electrodes by rapid thermal annealing;
 - d) bonding a temporary substrate to said LED epitaxial structure and said first electrode;
 - e) removing said substrate provided in step a);
 - f) forming a mirror beneath said LED epitaxial structure;
 - g) plating a permanent substrate beneath said mirror; and
 - h) removing said temporary substrate.
- Claim 2 (withdrawn): The method as claimed in claim 1, wherein said substrate provided in step a) is a GaAs substrate, a sapphire substrate or an InP substrate.

- Claim 3 (withdrawn): The method as claimed in claim 1, wherein said LED epitaxial structure is made from a material selected from the group consisting of Ga_xAl_yIn_{1-x-y}N, (Al_xGa_{1-x})_yIn_{1-y}P, In_xGa_{1-x}As, ZnS_xSe_{1-x}; wherein 0≤x≤1, 0≤y≤1.
- Claim 4 (withdrawn): The method as claimed in claim 1, wherein said metal contact layer is partially etched to retain a portion beneath said first electrode.
- Claim 5 (withdrawn): The method as claimed in claim 1 further depositing a transparent conductive film between said first electrode and said metal contact layer.
- Claim 6 (withdrawn): The method as claimed in claim 1, wherein said temporary substrate is a glass substrate.
- Claim 7 (withdrawn): The method as claimed in claim 1, wherein said temporary substrate is bonded to said LED epitaxial structure with epoxy or wax.
- Claim 8 (withdrawn): The method as claimed in claim 1, wherein said mirror is a metal capable of forming high bandgap with said LED epitaxial structure.
- Claim 9 (withdrawn): The method as claimed in claim 8, wherein said mirror is made from a material selected from the group consisting of Ag, Pt, Pd, Au, Au/Zn, Au/Be, Au/Ge, Au/Ge/Ni, In, Sn, Al, Zn, Ge and Ni, or mixtures thereof.
- Claim 10 (withdrawn): The method as claimed in claim 1, wherein said mirror is made from a composite of a metal with a low refractivity and an insulating layer with a high refractivity, and said insulating layer is adjacent to said LED epitaxial structure.
- Claim 11 (withdrawn): The method as claimed in claim 10, wherein said composite is selected from the group consisting of Al/Al₂O₃,

Al/SiO₂, Al/MgF₂, Pt/Al₂O₃, Pt/SiO₂, Pt/MgF₂, Al/Al₂O₃, Al/SiO₂, Al/MgF₂, Au/Al₂O₃, Au/SiO₂, Au/MgF₂, Ag/Al₂O₃, Ag/SiO₂, Ag/MgF₂.

- Claim 12 (withdrawn): The method as claimed in claim 1, wherein said permanent substrate is plated beneath said mirror other than predetermined saw streets.
- Claim 13 (currently amended): A light emitting diode having a plated substrate with a mirror, comprising:
 - an LED epitaxial structure sequentially comprising a second cladding layer, an active layer, a first cladding layer, a window and a metal contact layer, wherein said second cladding layer is partially exposed, wherein said active layer is made from a material selected from the group consisting of (Al_xGa_{1-x})_yIn_{1-y}P, Ga_xAl_yIn_{1-x-y}N, In_xGa_{1-x}As, and ZnS_xSe_{1-x}, 0≤x≤1, 0≤y≤1;
 - a first electrode formed on said metal contact layer;
 - a second electrode formed on said exposed second cladding layer;
 - a mirror formed beneath said LED epitaxial structure; and
 - a permanent metal substrate plated beneath said mirror and retaining sawing streets without plating the substrate thereon;
 - wherein said mirror is made from a composite, a metal or an alloy selected from the group consisting of:
 - Al/MgF_2 , Pt/Al_2O_3 , Pt/SiO_2 , Pt/MgF_2 , Au/SiO_2 , Au/MgF_2 , Ag/MgF_2 ;
 - Ag, Au, Au/Zn, Au/Be, Au/Ge, Au/Ge/Ni and Zn, or mixtures thereof when said active layer LED epitaxial structure is made from (Al_xGa_{1-x})_yIn_{1-y}P;
 - Ag, Pt, Pd, Al, and Ni, or mixtures thereof when said <u>active layer</u>

 <u>LED epitaxial structure</u> is made from $Ga_xAl_yIn_{1-x-y}N$, $0 \le x \le 1$, $0 \le y \le 1$;
 - Ag, Au, Au/Zn, Au/Be, Au/Ge, Au/Ge/Ni and Zn, or mixtures thereof when said active layer LED epitaxial structure is made from

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 $In_xGa_{1-x}As$, $0 \le x \le 1$, $0 \le y \le 1$; or

Ag, Pt, Pd, Au/Zn, Au/Be, Au/Ge, Au/Ge/Ni, Al and Ni, or mixtures thereof when said active layer LED epitaxial structure is made from ZnS_xSe_{1-x} , $0 \le x \le 1$, $0 \le y \le 1$.

Claim 14 (canceled)

Claim 15 (original): The light emitting diode as claimed in claim 13 further comprising a transparent conductive film between said first electrode and said metal contact layer.

Claims 16-25 (canceled)